# NILindustrialday 2025



# micro resist

v20250411a

## May 5 and 6, Vienna

Day 1 – CEST	<u>May 5</u>	
09:00	11:00	Setting up of exhibition
11:00	12:30	Arrival of participants / registratiom / exhibition / sandwich lunch
12:30	bmimi, MRT, PROFACTOR	Welcome and opening of the NILindustrialday 2025

Session 1 – Session chair: Jan Stensborg (Stensborg A/S)					
12:40	NILT	Theodor Nielsen	Nano-optics solutions by NIL for consumer electronics applications		
13:00	Dispelix	Mikhail Omelyanovich	Durable, ultralight, high-performance AR waveguides		
13:20	EVG	Johanna Rimböck	Status & Perspectives of Nanoimprint Lithography: Focus on sustainable high-volume manufacturing		
13:40	imec	Eleonora Storace	Waveguide displays for Augmented Reality: Enhancing performance through design for manufacturability and advanced lithography		
14:00	micro resist technology	Maria Russew	Recent material innovations for sacrificial and non-sacrificial NIL enabling high performance applications		
14.20			Coffee break / exhibition		

#### Session 2 – Session chair: Vincent Einck (Myrias Optics)

15:00	IMS CHIPS	Astrit Shohi	Mastering the Master: Nanopatterning beyond binary features
15:20	PROFACTOR	Michael Mühlberger	Nanoimprinting for polymer-based augemented reality devices
15:40	IBA Heiligenstadt	Marcus Soter	Nanoimprint Lithography for Medical Devices: Using FluidFM and NIL to improve blood-contacting surfaces
16:00	SINTEF	Christopher Dirdal	NIL for scalable MEMS-metasurfaces and SERS sensors with applications within medical and environmental sensing

#### 16:20 Coffee break / exhibition

#### Session 3 – Session chair: Pavel Kulha (PROFACTOR)

17:00	Myrias Optics	Vincent Einck	Commercialization of All-Inorganic Direct NIL: Manufacturing and wafer level test
17:20	SCIL Nanoimprint	Erik Peters	SCIL: tools and materials for direct patterning of advanced nano- optics
17:40	Nanoscribe	Jochen Zimmer	Two-Photon Grayscale Lithography (2GL) for masters without stitching seams and tilt-related imperfections
18:00	Snap	Atul Chaudhari	Engineering Functional Materials for Next-Gen AR Optics
18-20			Break

#### Exhibition:

18:40











Departure for social event





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Federal Ministry Innovation, Mobility and Infrastructure Republic of Austria

# NILindustrialday 2025

## **SOLYMORE**

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micro resist techno

### May 5 and 6, Vienna

Day 2 - May 6

CEST	
08:00	

08:40	Exhibition /	arrival o	of participants
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08:40 MRT & PROFACTOR Opening of day 2 of the NILindustrialday 2025

Session 4 – Session chair: Mirko Lohse (MRT)				
08:50	SUSS MicroTec	Amir Sharghi	From AR to Co-Packaging: a vision for integrated optics	
09:10	Tokyo University of Science	Jun Taniguchi	Fabrication of NIL mold and application technology using silver ink transfer	
09:30	Tekscend Photomasks	Martin Sczyrba	Advanced NIL master manufacturing technologies for XR systems and meta-optics applications	
09:50	SAL	Clement Fleury	8-inch NIL master fabrication for metasurfaces and color filter applications	
10:10	Germanlitho	Ran Ji	Introduction to NIL industrial applications and market trends	
10:30	Joanneum Research	Daniel Borstner	Functional structures in microfluidics devices fabricated by Roll-to-Roll UV-nanoimprint lithography	
10:50			Coffee break / exhibition	

Session 5 – Session chair: Thomas Achleitner (EVG)

11:50 UpNano Markus Lunzer Adaptive Resolution 2-Photon Lithography for highly-defined large area NIL masters  12:10 Morphotonics Bram Titulaer Advancements in mass production of nano and micron structured surfaces using large-area NIL  12:30 Heidelberg Instruments Julia Stark NanoFrazor thermal scanning probe lithography: Nanometer precise grayscale patterning for NIL master templates  12:50 Himax IGI Glen de Villafranca High Volume Wafer Scale Optics: From mastering to mass production  13:10 MRT & PROFACTOR Final announcements	11:30	Scia systems	Tabea Albert	AR technology
surfaces using large-area NIL  12:30 Heidelberg Instruments  Julia Stark  NanoFrazor thermal scanning probe lithography: Nanometer precise grayscale patterning for NIL master templates  12:50 Himax IGI  Glen de Villafranca  High Volume Wafer Scale Optics: From mastering to mass production	11:50	UpNano	Markus Lunzer	
Instruments precise grayscale patterning for NIL master templates  12:50 Himax IGI Glen de Villafranca High Volume Wafer Scale Optics: From mastering to mass production	12:10	Morphotonics	Bram Titulaer	Advancements in mass production of nano and micron structured surfaces using large-area NIL
production	12:30	Ū	Julia Stark	
13:10 MRT & PROFACTOR Final announcements	12:50	Himax IGI	Glen de Villafranca	· ·
	13:10	MRT & PROFACT	OR	Final announcements

Lunch / networking 13:20

End of exhibition and 14:30 of NILindustrialday 2025

Exhibition:















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